

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s): Michio YANAGI, et al.

Group Art Unit: 2872

Serial No.: 10/630,888

Examiner: L. Boutsikaris

Filed: July 30, 2003

For: METHOD OF MANUFACTURING ND FILTER, AND APERTURE DEVICE AND CAMERA HAVING ND FILTER

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

Mail Stop RCE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:


This Information Disclosure Statement is being filed in accordance with 37 C.F.R. §§ 1.56 and 1.97 and 1.98 and supplements the Information Disclosure Statement and PTO Form-1449 previously filed with the United States Patent and Trademark Office on January 28, 2005. The Examiner is respectfully requested to fully consider the items and to independently ascertain their teaching. Applicants submit herewith a corrected Partial English Translation of Japanese Office Action of JP Application No. 2002-220762 cited in the prior filed IDS to address inadvertent typographical error, namely, "1/λ" should be --1/4 λ --.

- ☒ This document is being filed within three (3) months of the filing date of the application
- ☐ A check for the requisite fee of \$180 is enclosed.
- ☐ This document is being concurrently filed with the above-identified application
- ☐ This document is being concurrently filed with an Request for Continued Examination (RCE)
- ☐ This document is being filed prior to a first Office Action
- ☐ This document is accompanied by a Search Report/Communication cited in a corresponding PCT or foreign counterpart application.

- ☒ The Commissioner is hereby authorized to charge any additional fees which may be required for this Information Disclosure Statement, or credit any overpayment to Deposit Account No. 13-4503, Order No. 1232-5094.

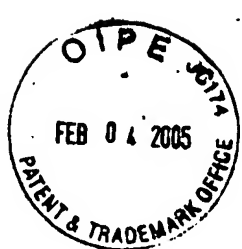
Respectfully submitted,  
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Dated: 2/4/05

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**Corrected Translation of Examiner's Comments in Japanese Official Actions**

**1) For JP Appln. 2002-220762 (translation of a)**

The cited references are (1) JP 07-063915 A, (2) JP 2000-352736 A, (3) JP 2000-119846 A, and (4) JP 11-038206 A.

**For Claims 1-6, 10 and 11:**

The reference (1) discloses a ND filter which is obtained by forming at least two kinds of layers, and which has an uppermost layer with a thickness of  $\frac{1}{4} \lambda$  and refractive index of 1.5 or less. The reference (2) discloses a ND filter having a density distribution obtained by halftone printing in which dots are evaporated onto a transparent sheet gradually or non-gradually while changing the size and pitch thereof. Hence, the inventions of claims 1-6, 10 and 11 are recognized as easily invented by the skilled person by adopting the matters shown in the reference (2) to the layers other than the uppermost layer in the reference (1). In addition, the design of the distance between the mask and the substrate is appropriately chosen by the skilled person in accordance with a pattern to be formed with an usual technical knowledge. The design of the substrate temperature is also appropriately chosen by the skilled person (Note that the reference (3) teaches to execute the process in a temperature region between a temperature at which clack or the like is not caused and a temperature higher than or equal to 120 degree C, if the substrate is made of plastic.).

**For Claims 7-9:**

The reference (4) discloses a ND filter in which the thickness thereof is continuously changed to form a gradation density distribution, and the method for manufacturing the same.

Hence, the inventions of claims 7-9 can be easily invented by adopting the matter shown in the reference (4) to the layers other than the uppermost layer in the reference (1).

**2) For JP Appln. 2002-220770 (translation of b)**

The cited references are (1) JP 11-190866 A, (2) JP 03-264668 A, and (3) JP 2000-119846 A.

For Claims 1-10:

The inventions of claims 1-10 are recognized as easily invented by the skilled person by forming layers other than the uppermost layer shown in the reference (1) to have the gradation density distribution by using the film forming device shown in the reference (2) so as to making a continuously changing of the thickness of the layer. In addition, although the mask shown in the reference (2) uses a tetrameric blade member, the design of the mask, i.e., making it slit like form or integrally rotating it (rotating the mask and the substrate integrally), is appropriately chosen by the skilled person. The design of the substrate temperature is also appropriately chosen by the skilled person (Note that the reference (3) teaches to execute the process in a temperature region between a temperature at which clack or the like is not caused and a temperature higher than or equal to 120 degrees C, if the substrate is made of plastic.).



↑AFFIX CUSTOMER NO. LABEL ABOVE ↑

<b>FORM PTO-1449</b>  <b>INFORMATION DISCLOSURE CITATION</b>	Attorney Docket: 1232-5094	Serial No.: 10/630,888
	Applicant: Michio YANAGI, et al.	
	Filing Date: July 30, 2003	Group Art Unit: 2872

**U.S. PATENT DOCUMENTS**

Examiner Initial		Patent Number	Publication Date	Name	Class	Sub-Class	Filing Date
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

**FOREIGN PATENT DOCUMENTS**

Examiner Initial		Patent Number	Publication Date	Country	Class	Sub-Class	Translation
	AL						
	AM						
	AN						
	AO						
	AP						
	AR						

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Papers, etc.)**

	AS	Partial English Translation of Japanese Office Action of JP Application No. 2002-220762.
	AT	Partial English Translation of Japanese Office Action of JP Application No. 2002-220770.

Examiner	Date Considered
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP §609.  
Draw line through citation if not in conformance and not considered.  
Include copy of this form with next communication to Applicant.